Y

	Application No.	Applicant(s)
Notice of Allowability		
	10/749,726 Examiner	HER ET AL. Art Unit
	LAMINIE	A Come
	Lan Vinh	1765
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to <u>Amendment and response filed on 2/15/2006</u> .		
2. The allowed claim(s) is/are 1.4 and 8-24.		
3. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).		
a) ☐ All b) ☐ Some* c) ☐ None of the:		
1. Certified copies of the priority documents have been received.		
2. Certified copies of the priority documents have been received in Application No		
3. Copies of the certified copies of the priority documents have been received in this national stage application from the		
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:		
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.  THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		
4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.		
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.		
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached		
1)  hereto or 2)  to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date		
Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).		
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.		
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5 🗍 Notice of Informal P	Stant Application (PTO 152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summary	atent Application (PTO-152)
	Paper No./Mail Dat	(F10-413), :e
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date</li> </ol>	8), 7. 🛛 Examiner's Amendr	nent/Comment
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. Examiner's Stateme	ent of Reasons for Allowance
-	9.	
		Lan Vinh AU 1765

**Art Unit: 1765** 

## **DETAILED ACTION**

## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

On page 1 of the specification, "now US Patent number 6,702,954" has been inserted after "October 19, 2000"

## Allowable Subject Matter

2. Claims 1, 4,8-24 are allowed.

The following is an examiner's statement of reasons for allowance:

Regarding claims 1, 19, 22, the Applicants have presented a persuasive argument, see pages 7-9 of the response filed on 2/15/2006 that the cited prior art of record, taken alone or in combination, fails to disclose a method of suppressing the removal rate of an underlying silicon-containing dielectric layer during CMP comprises a step of polishing the barrier layer using a chemical-mechanical polishing slurry comprising an amount of an agent selected from the group consisting of lysine and arginine sufficient to suppress the rate at which said underlying silicon-containing dielectric layer is removed by at least about 50% as compared to the rate at which said underlying silicon-containing dielectric layer would be removed if said agent was not present in said slurry

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lan Vinh whose telephone number is 571 272 1471. The examiner can normally be reached on M-F 8:30-5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571 272 1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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April 26, 2006